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FIRST NAMED INVENTOR CONFIRMATION NO. APPLICATION NO. FILING DATE ATTORNEY DOCKET NO. 02/22/2002 Rajiv K. Singh 1904 10/082,010 5853-224 **EXAMINER** 7590 Gregory A. Nelson, Esq. UMEZ ERONINI, LYNETTE T Akerman, Senterfitt & Eidson, P.A. ART UNIT PAPER NUMBER 222 Lakeview Avenue, Suite 400 P.O. Box 3188

1765
DATE MAILED: 01/11/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

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Office Action Summary	Application No.	Applicant(s)	
	10/082,010	SINGH ET AL.	
	Examiner	Art Unit	
	Lynette T. Umez-Eronini	1765	
The MAILING DATE of this communication appeared for Reply	ppears on the cover sheet with	the correspondence addres	is
A SHORTENED STATUTORY PERIOD FOR REP WHICHEVER IS LONGER, FROM THE MAILING I - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICA 1.136(a). In no event, however, may a reply d will apply and will expire SIX (6) MONTH: tte, cause the application to become ABAN	ATION.  y be timely filed  S from the mailing date of this commu	
Status			
1) Responsive to communication(s) filed on 27	October 2005.		
2a) ☐ This action is <b>FINAL</b> . 2b) ☑ Th	is action is non-final.		
3) Since this application is in condition for allow	ance except for formal matters	s, prosecution as to the me	rits is
closed in accordance with the practice under	Ex parte Quayle, 1935 C.D. 1	1, 453 O.G. 213.	
Disposition of Claims			
4) ⊠ Claim(s) <u>1-6,8-10,19-26 and 29-37</u> is/are per 4a) Of the above claim(s) is/are withdra 5) □ Claim(s) is/are allowed.  6) ⊠ Claim(s) <u>1,5,6,8-10,19-21,26 and 29-37</u> is/are 7) □ Claim(s) <u>2-4 and 22-25</u> is/are objected to.  8) □ Claim(s) are subject to restriction and/	awn from consideration. e rejected.		
Application Papers			
9) ☐ The specification is objected to by the Examin 10) ☑ The drawing(s) filed on 25 February 2002 is/a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction 11) ☐ The oath or declaration is objected to by the Examination is objected.	re: a) $\square$ accepted or b) $\square$ objection of a drawing(s) be held in abeyance ction is required if the drawing(s)	. See 37 CFR 1.85(a). is objected to. See 37 CFR 1.	. ,
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureat* * See the attached detailed Office action for a list	nts have been received.  Its have been received in Appropriate ority documents have been recau (PCT Rule 17.2(a)).	lication No ceived in this National Stag	je
Attachment(s)  1) Notice of References Cited (PTO-892)	4) Interview Sum		
<ul> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date</li> </ul>		tail Date mal Patent Application (PTO-152)	)

#### **DETAILED ACTION**

This communication is in response to Applicants' Remarks in Amendment filed 10/27/2005, which was persuasive in distinguishing a nanosize and nanoporous particle and showing the former prior art failed to teach a nanoporous particle. Hence, a new rejection is presented.

### Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 3. Claims 1, 5, 6, 9, and 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Garg (US 6,045,577 in view of Meyer et al. (US 5,055,019).

Garg teaches nano-sized powder of alpha alumina having silica coating thereon (column 5, lines 7-10). Garg further teaches a polishing slurry is comprised of a alumina powder has a silica coating wherein 95% of the particles have widths of from 20 to about 50 nanometers while less than 5% have particle sizes greater than 100 nanometers and is dispersed in a liquid dispersion medium (claims 6 and 9). The aforementioned reads on,

A slurry for chemical mechanical polishing (CMP), comprising:

a bulk solution; and

a plurality of particles, in claim 1; and

encompasses an average particle size of said nanosize comprising particles is less than 500 nm, in claim 9 and is from 200 to 500 nm, in claim 10.

Garg differs if failing to teach a plurality of nanoporous comprising particles, in claims 1, 5, 6, and 9.

Meyer discloses boehmitic alumina compounds having Al<sub>2</sub>O<sub>3</sub> and the compounds have a pore radii in the range of 3 to 100 nm (Abstract and column 1, lines 6-10), which reads on a plurality of nanoporous comprising particles.

Since Meyer illustrates a plurality of nanoporous comprises particles is known, then it would have been obvious to one having ordinary skill in the art at the time the invention was made to modify Garg's slurry by employing compounds having a pore radii in the nm range as taught by Meyer, including applicants' specifically claimed range because such compounds can be used in polishing agents (Meyer, column 1, lines 11-16).

4. Claims 17 and 35 are rejected under 35 U.S.C. 103(a) as being unpatentable over Garg (US '577) in view if Meyer (US'019) as applied to claim 1 above.

Garg in view of Meyer differs in failing to teach the slurry wherein a porosity of said nanoporous particles is in a range from 10 to 60%, **in claim 17**; and wherein a concentration of said composite particles in said slurry is from approximately 1% to 40% by weight, **in claim 35**.

However, Garg in view of Meyer illustrates the specific combination of bulk solution and nanoporous particles and nano-sized alpha alumina particles having a coating is known. As a result, it would have been obvious to one of ordinary skill in the art at the time the invention was made to select any porosity of the nanoporous particles and weight percent of the alumina coated silica particles (same as applicants' composite particles) in the Garg reference that would effectively accomplish the disclosed composition because it has been held that there is no invention where the difference in proportions is not critical and was ascertained by routine experimentation because the determination of workable ranges is not considered inventive. See In re Swain and Adams, 70 USPQ 412 (CPA 1946).

5. Claims 8, 19-21, 31-34, and 36-37 are rejected under 35 U.S.C. 103(a) as being unpatentable over Garg (US '577) in view or Meyer (US '019) as applied to claim 1 above, and further in view of Li et al. (IS 6,458,017 B1).

Garg in view of Meyer differ in failing to teach the slurry comprises at least one species selected from the group consisting of a polyhalide ion, I<sub>2</sub>, Br<sub>2</sub>, and F<sub>2</sub>, in claim 8;

at least one passivating additive, in claim 19; at least one complexing agent, as specified in claims 20-21; at least on salt, in claims 31-32; an pH 6-13 and 8-11, respectively, in claims 33-34; and at least one oxidizer, in claims 36-37.

Li teaches and illustrates the specific combination of additives in a polishing slurry comprising oxidizers (column 5, lines 49-50); chelate complex (same as applicants' complexing agent), (column 5, lines 55-56); benzotriazole (same as applicants' passivating agent), (column 6, lines 2-3); surfactants (column 6, lines 15-21); an intermediate pH of 3-7 (column 6, lines 2-3) and pH values higher than 10 (column 6, lines 24-25); and suspension media comprising IBr<sub>2</sub> and BrF<sub>3</sub> (column 9, lines 12-14) along with a nanometer size particle (column 3, lines 26-27) is known.

Hence it would have been obvious to one having ordinary skill in the art at the time of the claimed invention to modify Garg in view of Meyer by adding known additives as taught by Li to a polishing solution that would effectively accomplish the disclosed composition.

6. Claims 29 and 30 is rejected under 35 U.S.C. 103(a) as being unpatentable over Garg (US '577) in view of Meyer (US '019) as applied to claim 1 above, and further in view of Sahota et al. (US 6,503,418 B2).

Garg in view of Meyer differs in failing to teach wherein said selective additive comprises at least one polymer, in claim 29; and wherein said polymer is at least on selected from the group consisting of polyethylene oxide (PEO), polyacrylic acid

(PAAP), polyacryamide (PAM), polyvinylalcohol (PVA) and polyalkylamine (PAH), in claim 30.

Sahota teaches organic additive such as PVA and PAA, which suppresses formation of precipitates during cmp of copper metal layer (Abstract and column 4, lines 37-47 and claim 1).

It would have been obvious to one having ordinary skill in the art at the time of the claimed invention to modify Garg in view of Meyer by using a polymer additives as taught by Sahota for the purpose of suppressing formation of precipitates during cmp of copper metal layer (Sahota, column 4, lines 37-47).

### Allowable Subject Matter

- 7. Claims 2, 3, 4, 22, 23, 24, and 25 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 8. The following is a statement of reasons for the indication of allowable subject matter: As to claims 2, 3, 4, 23, and 25, the prior art of record taken alone or in combination fails to suggest, teach, and or render obvious at least and selective adsorption additive wherein said selective adsorption additive is in a concentration of from 6 to 1,000 critical micelle concentration (CMC) when said selective adsorption additive is non-ionic and from 1 to 1,000 CMC when selective adsorption additive is zwitterionic, anionic or cationic, said selective adsorption additive self assembling in said bulk solution, in combination with the rest of the limitations of the said claims.

## Response to Arguments

9. Applicant's arguments, see Remarks, filed 10/27/2005, with respect to the rejection(s) of claim(s) 1, 6, 9, and 18 under 102(b) over Garg (US 6,048,577) and claim(s) 8, 19-21, 31-34, and 36, and 37 under 103(a) over Garg (US '577) as applied to claim 1, and further in view of Li et al. (US 6,458017) have been fully considered and are persuasive. Therefore, the rejection has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made in view of claims 1, 6, 8, 9, 19-21, and 31-37.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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January 5, 2005

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